

Search Notes

Application No.

09/912,398

Examiner

Mary C Hogan

Applicant(s)

INANAMI ET AL.

Art Unit

2123

SEARCHED

| Class | Subclass | Date | Examiner |
|-------|----------|------------|----------|
| 703 | 2,20 | 12/16/2004 | MCH |
| 700 | 105-107 | 12/16/2004 | MCH |
| 700 | 19,182 | 12/16/2004 | MCH |
| 716 | 21 | 12/16/2004 | MCH |
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INTERFERENCE SEARCHED

| Class | Subclass | Date | Examiner |
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**SEARCH NOTES
(INCLUDING SEARCH STRATEGY)**

| | DATE | EXMR |
|---|------------|------|
| Inventor Name Search: EAST, IEEE | 12/15/2004 | MCH |
| IEEE: charged particle beam, character projection, semiconductor <and> manufacture <and> order <and> design <and> cost <and> | 12/16/2004 | MCH |
| ACM: character projection,manufacture, mask customer design | 12/16/2004 | MCH |
| IEEE: semiconductor <and> design <and> 'real time' <and> network | 12/16/2004 | MCH |
| EAST:character projection,circuit pattern,specification,parameter,cost,ti me,network,charged particle beam,mask,aperture,order | 12/16/2004 | MCH |
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